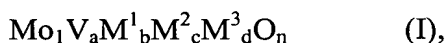


IN THE SPECIFICATION

Please replace the paragraph beginning at page 1, line 2, with the following rewritten paragraph:

The present invention relates to multimetal oxide materials of the stoichiometry I



where

$\text{M}^1$  is at least one of the elements from the group consisting of Te and Sb;

$\text{M}^2$  is at least one of the elements from the group consisting of Nb, Ti, W, Ta and Ce;

$\text{M}^3$  is at least one of the elements from the group consisting of Pb, Ni, ~~Co~~ Co, Bi, Pd, Ag, Pt, Cu, Au, Ga, Zn, Sn, In, Re, Ir, Sm, Sc, Y, Pr, Nd and Tb;

a is from 0.01 to 1,

b is from > 0 to 1;

c is from > 0 to 1;

d is from > 0 to 0.5 and

n is a number which is determined by the valency and frequency of the elements other than oxygen in (I),

whose X-ray diffraction pattern has reflections h, i and k whose peaks are at the diffraction angles  ~~$2\theta$   $22.2 \pm 0.5^\circ$~~   $2\theta$   $22.2 \pm 0.5^\circ$  (h),  ~~$27.3 \pm 0.5^\circ$~~   $27.3 \pm 0.5^\circ$  (i) and  ~~$28.2 \pm 0.5^\circ$~~   $28.2 \pm 0.5^\circ$  (k),

- the reflection h being the one with the strongest intensity within the X-ray diffraction pattern and having an FWHH of not more than  $0.5^\circ$ ,

- the intensity  $P_i$  of the reflection i and the intensity  $P_k$  of the reflection k fulfilling the relationship  $0.65 \leq R \leq 0.85$ , where R is the intensity ratio defined by the formula

$$R = P_i / (P_i + P_k)$$

and

the FWHH of the reflection i and of the reflection k being in each case  $1^\circ$ ,

wherein the at least one multimetal oxide material (I) is one whose X-ray diffraction pattern has no reflection with the peak i position  $2(\Theta) = 50.0 \pm 0.3^\circ$   $2\theta = 50.0 \pm 0.3^\circ$ .

Please replace the paragraph beginning at page 2, true line 28, with the following rewritten paragraph:

In the publications cited, this is attributable to the fact that, as a result of their preparation, these multimetal oxide materials are substantially present in crystalline form having a specific crystal structure, wherein their X-ray diffraction pattern has reflections with a strong intensity at the  $2\theta$  peak positions  ~~$22.1 \pm 0.3^\circ, 28.2 \pm 0.3^\circ, 36.2 \pm 0.3^\circ, 45.2 \pm 0.3^\circ$~~  and  ~~$50.0 \pm 0.3^\circ$~~   $22.1 \pm 0.3^\circ, 28.2 \pm 0.3^\circ, 36.2 \pm 0.3^\circ, 45.2 \pm 0.3^\circ$  and  $50.0 \pm 0.3^\circ$ .

Please replace the paragraph beginning at page 3, line 1, with the following rewritten paragraph:

A second specific crystal structure in which the relevant multimetal oxide materials can occur is referred to as a rule as the i phase. Typical of its X-ray diffraction content, according to the abovementioned publications, is, inter alia, that it has reflections of the strongest intensity at the  $2\Theta$  peak positions  ~~$22.2 \pm 0.4^\circ, 27.3 \pm 0.4^\circ$  and  $28.2 \pm 0.4^\circ$~~   $22.2 \pm 0.4^\circ, 27.3 \pm 0.4^\circ$  and  $28.2 \pm 0.4^\circ$ , in contrast to the k phase in which, however, there is no reflection at the  $2\Theta$  peak position  ~~$50.0 \pm 0.3^\circ$~~   $50.0 \pm 0.3^\circ$ .

Please replace the paragraph beginning at page 5, true line 6, with the following rewritten paragraph:

In addition to the reflections h, i and k, the X-ray diffraction pattern of novel multimetal oxide materials (I) contains, as a rule, further reflections whose peaks are at the following diffraction angles ( $2\Theta$   $2\ominus$ ):

$$\cancel{9.0 \pm 0.4^\circ} \quad \underline{9.0 \pm 0.40^\circ} \text{ (l),}$$

$$\cancel{6.7 \pm 0.4^\circ} \quad \underline{6.7 \pm 0.4^\circ} \text{ (o) and}$$

$$\cancel{7.9 \pm 0.4^\circ} \quad \underline{7.9 \pm 0.4^\circ} \text{ (p).}$$

Please replace the paragraph beginning at page 5, true line 13, with the following rewritten paragraph:

It is furthermore advantageous if the X-ray diffraction pattern additionally contains a reflection whose peak is at the diffraction angle ( $2\Theta$ ) of  $\cancel{45.2 \pm 0.4^\circ} \quad \underline{45.2 \pm 0.4^\circ}$  (q).

Please replace the paragraph beginning at page 5, true line 16, with the following rewritten paragraph:

Frequently, the X-ray diffraction pattern of multimetal oxide materials (I) also contains the reflections  $\cancel{29.2 \pm 0.4^\circ} \quad \underline{29.2 \pm 0.4^\circ}$  (m) and  $\cancel{35.4 \pm 0.4^\circ} \quad \underline{35.4 \pm 0.4^\circ}$  (n) (peak positions).

Please replace the paragraph beginning at page 16, true line 33, with the following rewritten paragraph:

As stated above, what is important according to the invention is that the multimetal oxide materials (I) to be used according to the invention have an X-ray diffraction pattern (in this document, always based on Cu-K $\alpha$  radiation) which has reflections h, i and k whose peaks are at the diffraction angles (2 $\theta$ ) ~~22.2 + 0.4°~~ 22.2 ± 0.4° (h), ~~27.3 + 0.4°~~ 27.3 ± 0.4° (i) and ~~28.2 + 0.4°~~ 28.2 ± 0.4° (k),

- reflection h being the one with the strongest intensity within the x-ray diffraction pattern and having an FWHH of not more than 0.5°,
- intensity P<sub>i</sub> of the reflection i and the intensity P<sub>k</sub> of the reflection k fulfilling the relationship  $0.65 \leq R \leq 0.85$ , where R is the intensity ratio defined by the formula

$$R = P_i / (P_i + P_k)$$

and

- the FWHH of the reflection i and of the reflection k is in each case  $\leq 1^\circ$ .

Please replace the paragraph beginning at page 17, true line 11, with the following rewritten paragraph:

At the same time, the X-ray diffraction pattern should have no reflections with the peak position ~~2 $\theta$  = 50.0 + 0.3°~~  $2\theta = \underline{50.0 \pm 0.3^\circ}$ .